

TITLE OF THE INVENTION

LINEAR MOTOR AND STAGE APPARATUS, EXPOSURE APPARATUS,
AND DEVICE MANUFACTURING METHOD USING THE SAME

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FIELD OF THE INVENTION

The present invention relates to a linear motor suitably used as, e.g., a driving source for a stage apparatus mounted on an exposure apparatus or the like for the manufacture of a semiconductor device or the like, and a stage apparatus, exposure apparatus, and device manufacturing method using the same.

BACKGROUND OF THE INVENTION

Fig. 12 shows the arrangement of the permanent magnets of a linear motor according to one prior art. Fig. 12 shows only one of two permanent magnet groups opposing each other through a holding member 7. Permanent magnets 110a and 110b alternately arrayed on the holding member 7 have a non-rectangular parallelepiped shape with corners being cut off. The permanent magnets 110a and 110b are arrayed such that their magnetisms (N and S poles) are alternately opposite. Also, the thicknesses and widths of the permanent magnets 110a and 110b are so adjusted as to generate an ideal sine wave magnetic field in a space between opposing yokes and the permanent magnet groups.

According to the above prior art, to make the sine wave magnetic field to generate an ideal sine wave, the thicknesses and widths of the permanent magnets must locally differ. As the entire shape of each magnet is not a simple rectangular parallelepiped, each permanent magnet is difficult to fabricate with high precision, leading to a high cost. This problem has not been solved yet. The obtained magnetic field density is lower than that obtained with a rectangular parallelepiped permanent magnet, and the driving force of the linear motor is accordingly decreased.

SUMMARY OF THE INVENTION

The present invention has been made in view of the problems of the prior art that have not yet been solved, and has as its object to provide a linear motor which has an excellent driving performance with a small thrust ripple (thrust variations) while requiring a low cost and providing a high driving force, and which can accordingly largely contribute to an increase in positioning precision and productivity of a stage apparatus for holding a substrate, e.g., a wafer, of an exposure apparatus, and a stage apparatus, exposure apparatus, and device manufacturing method using the same.

In order to achieve the above object, a linear motor according to the present invention comprises

first magnets arrayed such that polarization directions thereof are periodically opposite, second magnets arrayed adjacent to the first magnets such that polarization directions thereof are periodically
5 opposite, and an electromagnetic coil opposing the first and second magnets to generate the Lorentz force by at least the first and second magnets, the second magnets are disposed such that the polarization directions thereof intersect those of the first magnets.

10 Preferably, the polarization directions of the second magnets intersect those of the first magnets at an angle of substantially 90°.

Preferably, the first and second magnets are rectangular parallelepiped permanent magnets.

15 Preferably, the electromagnetic coil comprises at least two electromagnetic coils disposed to oppose the first and second magnets and to be energized simultaneously.

20 Preferably, the first and second magnets are permanent magnets with the same shape.

Preferably, either one of the first and second magnets which is disposed at a terminal end has a volume smaller than those of other magnets.

25 Preferably, the first and second magnets generate a sine wave magnetic field.

According to the present invention, in a linear motor that generates a sine wave magnetic field with

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magnetic groups in which the polarization directions of
a plurality of magnets are alternately inverted, in
order to obtain an ideal sine wave magnetic field,
magnets are disposed between two magnets with opposite
5 polarization directions, such that their polarization
directions intersect those of the two magnets at an
angle of, e.g., substantially 90°.

An ideal sine wave magnetic field can be formed
by only arraying permanent magnets with the same
10 rectangular parallelepiped shapes while changing their
polarization directions.

When compared to generating an ideal sine wave
magnetic field by arraying magnets with opposite
polarization directions adjacent to each other while
15 locally machining the respective magnets to have
different shapes, a linear motor with a larger driving
force can be manufactured without requiring complicated
machining and accordingly at a lower cost.

In this manner, when a high-performance stage
20 apparatus having a low-cost linear motor with a large
driving force and small thrust ripple as a driving unit
is used as a wafer stage or the like in an exposure
apparatus, a high-performance exposure apparatus with
high positioning precision and excellent productivity
25 for a semiconductor device and the like can be realized.

Other features and advantages of the present
invention will be apparent from the following

description taken in conjunction with the accompanying drawings, in which like reference characters designate the same or similar parts throughout the figures thereof.

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BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying drawings, which are incorporated in and constitute a part of the specification, illustrate embodiments of the invention and, together with the description, serve to explain the principles of the invention.

Fig. 1 is a schematic view showing the main part of a linear motor according to an embodiment of the present invention;

Fig. 2 is a graph showing the magnetic flux density of the linear motor movable element shown in Fig. 1;

Fig. 3 is a partial perspective view showing a practical example of the linear motor movable element;

Fig. 4 is a graph showing the magnetic flux density at the center of the linear motor movable element shown in Fig. 3;

Fig. 5 is a partial perspective view showing the first modification;

Fig. 6 is a graph showing the magnetic flux density at the terminal end of the linear motor movable element shown in Fig. 5;

Fig. 7 is a partial perspective view showing the second modification;

Fig. 8 is a graph showing the magnetic flux density at the terminal end of the linear motor movable
5 element shown in Fig. 7;

Fig. 9 is a schematic elevation showing an exposure apparatus;

Fig. 10 is a flow chart showing a device manufacturing process;

10 Fig. 11 is a flow chart showing a wafer process;
and

Fig. 12 is a partial perspective view showing a linear motor stator according to a prior art.

15 DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

The preferred embodiments of the present invention will be described with reference to the accompanying drawings.

Fig. 1 shows an embodiment. In this linear motor
20 M, a first permanent magnet group of first magnets 1a to 1d are arrayed in the x-axis direction and integrally connected on a holding member 7. The first permanent magnet group has the first magnets 1a and 1c arrayed such that their polarization directions are
25 periodically opposite, and the second magnets 1b and 1d arrayed adjacent to the first magnets 1a and 1c such that their polarization directions are periodically

opposite. A second permanent magnet group is arrayed on the other side of the holding member 7. A linear motor movable element 10 is thus formed. In the same manner as the first permanent magnet group, the second permanent magnet group has third magnets 5a and 5c arrayed such that their polarization directions are periodically opposite, and fourth magnets 5b and 5d arrayed adjacent to the third magnets 5a and 5c such that their polarization directions are periodically opposite.

The first magnets 1a and 1c and the third magnets 5a and 5c are arrayed such that they have the same polarization direction. The second magnets 1b and 1d and the fourth magnets 5b and 5d are arrayed such that they have opposite polarization directions.

One electromagnetic coil 2a is fixed on a yoke 3a, and the other electromagnetic coil 2b is fixed on a yoke 3b. The electromagnetic coils 2a and 2b opposing the linear motor movable element 10 make up a linear motor stator 20. When a current is supplied to the linear motor stator 20, a thrust in the x-axis direction is generated between the linear motor stator 20 and linear motor movable element 10. Alternatively, the group of first magnets 1a to 1d may form the stator of the linear motor, and the electromagnetic coils 2a and 2b may form the movable element of the linear motor. The holding member 7 may be formed of either a magnetic

or nonmagnetic material.

Both the first group of permanent magnets 1a to 1d and the second group of permanent magnets 5a to 5d are integrally connected while rotating the polarization directions (the direction of a straight line that connects the N and S poles with a smallest distance from the N pole toward the S pole in each magnet) of adjacent magnets sequentially (in one direction) through 90° . The second permanent magnets 1b and 1d between the first permanent magnets 1a and 1c with the opposite polarization directions, and the fourth permanent magnets 5b and 5d between the third permanent magnets 5a and 5c have polarization directions that intersect the polarization directions of the first permanent magnets 1a and 1c and those of the third permanent magnets 5a and 5c, respectively, at an angle of substantially 90° . The yokes 3a and 3b are fixed to be immobile relatively. Stationary magnetic fields are generated respectively in a space between the first and second permanent magnets 1a to 1d and the yoke 3a, and a space between the third and fourth permanent magnets 5a to 5d and the yoke 3b.

When at least four permanent magnets with polarization directions shifted from each other by substantially 90° are provided, as described above, the y component of the magnetic field present between the permanent magnets and yoke can have a sine waveform

with respect to the x-axis direction. Fig. 2 shows the y component of the magnetic flux density of this magnetic field.

Fig. 3 shows a practical example of the first permanent magnets 1a to 1d. Regarding the length in the moving direction (x-axis direction) of the linear motor movable element 10, each of the first permanent magnets 1a and 1c, the magnetic polarity of which is in the x-axis direction, has a length of 18 mm, and each of the second permanent magnets 1b and 1d, the magnetic polarity of which is in the y-axis direction perpendicular to the x-axis direction, has a length of 18 mm. While all the magnets have a rectangular parallelepiped shape with the same size, they may have a non-rectangular parallelepiped shape. The thickness (y-axis direction) of each of the permanent magnets 1a to 1d is 10 mm, and the width (z-axis direction) thereof is 80 mm.

When a current is supplied to the electromagnetic coils 2a and 2b located in the sine wave magnetic fields of the linear motor M, the Lorentz force is generated between the permanent magnets 1a to 1d and the electromagnetic coils 2a and 2b, and the linear motor movable element 10 moves in the x-axis direction with respect to the linear motor stator 20.

Fig. 1 shows the electromagnetic coils 2a and 2b schematically. In fact, the electromagnetic coils 2a

and 2b are multi-phase coils each formed by arranging a plurality of coils at a predetermined interval in the x-axis direction. Hence, the current is supplied to a plurality of electromagnetic coils simultaneously,
5 which is multi-phase energization.

As an example of multi-phase energization, energization to two-phase coils will be considered. Assuming that the first coil is at one point (position x) in a sine wave magnetic field, when a constant
10 current is supplied to this coil, the thrust forms a sine wave with respect to the position x of the coil. If the current is I1 (constant value), this thrust can be expressed as:

$$F1(x) = K \cdot B \cdot I1 \cdot \sin(2\pi x / a)$$

15 where K is a constant determined by the coil, B is the amplitude of the magnetic flux density, and a is the wavelength of the sine wave.

Assume that the second coil is present at a position always at a constant distance of a/4 in the x
20 direction from the first coil and is integrated with the first coil. When a constant current is supplied to the second coil, the thrust forms a sine wave. If the current is I2 (constant value), this thrust can be expressed as:

$$\begin{aligned} F2(x) &= K \cdot B \cdot I2 \cdot \sin(2\pi (x + a/4) / a) \\ &= K \cdot B \cdot I2 \cdot \cos(2\pi x / a) \end{aligned}$$

by using the position x of the first coil.

When a current is supplied to the two-phase coils,
that is, the first and second coils, simultaneously,
the total thrust is:

$$F = F_1 + F_2$$

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$$= K \cdot B (I_1 \cdot \sin(2\pi x / a) + I_2 \cdot \cos(2\pi x / a))$$

When currents satisfying

$$I_1 = I \cdot \sin(2\pi x / a)$$

$$I_2 = I \cdot \cos(2\pi x / a)$$

(for I is a constant value)

10 in correspondence to the position x of the first coil
are supplied to the first and second coils,

$$F = K \cdot B \cdot I$$

is obtained.

Since the coils opposing the permanent magnets 1a
15 to 1d are the electromagnetic coils 2a and 2b, the
thrust is:

$$F = 2 \cdot K \cdot B \cdot I$$

In this manner, in an ideal sine wave magnetic
field, when the multi-phase coils are energized, the
20 thrust ripple decreases. In other words, the very much
smaller the error of the magnetic field is with respect
to the sine wave, the very much smaller the ripple can
be decreased in the total thrust.

In this manner, when a current is supplied to
25 multi-phase coils placed in a sine wave magnetic field
or approximately sine wave magnetic field, the thrust
becomes constant or almost constant, so an excellent

linear motor with a small thrust ripple can be obtained.

When the permanent magnet group of Fig. 3 is used, the y component of the magnetic field present in the space between the permanent magnets and the yoke

5 becomes close to an ideal sine wave, and an error with respect to an ideal sine wave can be set to 2% or less of the amplitude of the sine wave. Fig. 4 shows the 1/2-period wave of the y component. The broken line indicates an ideal sine wave, and the solid line
10 indicates the wave of a magnetic flux density obtained with the permanent magnet group of Fig. 3. The two waves almost coincide with each other.

Because a sine wave magnetic field can be generated in the space where the coil is present, the
15 space between the permanent magnets and the yoke can be effectively utilized, and the magnetic flux density can be increased. Consequently, the thrust of the linear motor can be increased.

When a sine wave current is supplied to the
20 multi-phase coils, the thrust ripple of the linear motor can be decreased. Hence, the thrust characteristics of the linear motor and the positioning characteristics of a stage apparatus using this linear motor can be greatly improved.

25 Fig. 5 shows a linear motor according to the first modification. As a permanent magnet 1e located at the terminal end of the permanent magnet group, this

linear motor uses a rectangular parallelepiped magnet with a smaller size in the x-axis direction and a smaller volume than those of the remaining permanent magnets 1a to 1d. In this manner, when the size in the x-axis direction of the permanent magnet 1e at the terminal end is decreased to be smaller than those of the remaining permanent magnets, i.e., 13 mm, the y component of the magnetic flux density generated by the permanent magnet group becomes close to an ideal sine wave. For example, even at the terminal end of the linear motor movable element 10, an error with respect to the ideal sine wave can be decreased to 5% or less of the amplitude of the sine wave.

Fig. 6 shows the 1/2-period wave of the y component at this terminal end. In Fig. 6, the right side (+x side) is the terminal end. The broken line indicates an ideal sine wave, and the solid line indicates the magnetic flux density obtained with the permanent magnet group of Fig. 5. The two waves almost coincide with each other.

Fig. 7 shows the second modification. Three permanent magnets 1f to 1h located at the terminal end side have smaller sizes in the x-axis direction and smaller volumes than those of the remaining permanent magnets 1a to 1d. when the sizes in the x-axis direction of the permanent magnets 1f to 1h at the terminal end are gradually decreased, i.e., 15 mm for

the permanent magnet 1f, 10 mm for the permanent magnet 1g, and 5 mm for the permanent magnet 1h, the y component of the magnetic flux density generated by this permanent magnet group becomes very close to a sine wave. For example, even at the terminal end of the linear motor movable element 10, the error with respect to the ideal sine wave can be decreased to as very small as 2% or less of the amplitude of the sine wave.

Fig. 8 shows the 1/2-period wave of the y component at this terminal end. The right side (+x direction) is the terminal end. The broken line indicates an ideal sine wave, and the solid line indicates the magnetic flux density obtained with the permanent magnet group of Fig. 7. The two waves almost coincide with each other.

In this manner, when one or more permanent magnets each with a small volume are arranged at the terminal end, a magnetic flux density distribution close to an ideal sine wave can be maintained even at the terminal end of the permanent magnet group. Thus, an excellent linear motor with a small thrust ripple until the terminal end, i.e., a small thrust ripple over a long stroke, can be provided.

Fig. 9 shows a semiconductor device manufacturing exposure apparatus having, as a wafer stage, a stage apparatus in which a linear motor M1 identical to that

described above is used as the driving unit. A guide
52 and linear motor stator 21 are fixed on a surface
plate 51. The linear motor stator 21 has multi-phase
electromagnetic coils, and a linear motor movable
5 element 11 has a permanent magnet group, in the same
manner as described above. The linear motor movable
element 11 is connected as a movable portion 53 to a
movable guide 54 serving as a stage. When the linear
motor M1 is driven, the movable guide 54 is moved in a
10 direction normal to the surface of the sheet of drawing.
The movable portion 53 is supported by a static
pressure bearing 55 with reference to the upper surface
of the surface plate 51 and by a static pressure
bearing 56 with reference to the side surface of the
15 guide 52.

A movable stage 57 serving as a stage arranged
astride the movable guide 54 is supported by a static
pressure bearing 58. The movable stage 57 is driven by
a linear motor M2 similar to the linear motor M1
20 described above. The movable stage 57 moves to the
right and left on the surface of the sheet of drawing
with reference to the movable guide 54. The movement
of the movable stage 57 is measured by using a mirror
59 and interferometer 60 fixed to the movable stage 57.

25 A wafer W as a substrate is held on a chuck
mounted on the movable stage 57. The circuit pattern
of a reticle R as the master is reduced and transferred

onto the wafer W by a light source 61 and projection optical system 62.

An embodiment of a device manufacturing method conducted by the above exposure apparatus will be described. Fig. 10 shows the flow of the manufacture of a semiconductor device (a semiconductor chip such as an IC or LSI, a liquid crystal panel, a CCD, or the like). In step 1 (design circuit), a semiconductor device circuit is designed. In step 2 (fabricate mask), a mask as the master with the designed circuit pattern is fabricated. In step 3 (manufacture wafer), a wafer is manufactured by using a material such as silicon. In step 4 (wafer process) called a pre-process, an actual circuit is formed on the wafer in accordance with lithography using the exposure apparatus by using the prepared mask and wafer. Step 5 (assembly) called a post-process is the step of forming a semiconductor chip by using the wafer fabricated in step 4, and includes an assembly process (dicing and bonding) and packaging process (chip encapsulation). In step 6 (inspection), inspections such as the operation confirmation test and durability test of the semiconductor device fabricated in step 5 are conducted. After these steps, the semiconductor device is completed and shipped (step 7).

Fig. 11 shows the detailed flow of this wafer process. In step 11 (oxidation), the wafer surface is

oxidized. In step 12 (CVD), an insulating film is
formed on the wafer surface. In step 13 (form
electrode), an electrode is formed on the wafer by
vapor deposition. In step 14 (implant ion), ions are
5 implanted in the wafer. In step 15 (resist processing),
a photosensitive agent is applied to the wafer. In
step 16 (exposure), the above-mentioned exposure
apparatus exposes the wafer to the circuit pattern of
the mask. In step 17 (developing), the exposed wafer
10 is developed. In step 18 (etching), the resist is
etched except for the developed resist image. In step
19 (remove resist), an unnecessary resist after etching
is removed. These steps are repeated to form multiple
circuit patterns on the wafer. When the manufacturing
15 method of this embodiment is used, a high-integration
semiconductor device which is conventionally difficult
to manufacture can be manufactured.

As described above, according to this embodiment,
a high-performance linear motor with a high driving
20 force and a small thrust ripple can be manufactured at
a low cost by using a magnetic group with a simple
arrangement in which identical rectangular
parallelepiped permanent magnets are arrayed adjacent
to each other.

25 To use this linear motor in a stage apparatus
such as a wafer stage can largely contribute to an
improvement in transfer performance and productivity of

an exposure apparatus that manufactures a semiconductor device or the like.

The present invention is not limited to the above embodiments and various changes and modifications can
5 be made within the spirit and scope of the present invention. Therefore, to apprise the public of the scope of the present invention the following claims are made.